

L Number	Hits	Search Text	DB	Time stamp
1	107	"4522510" "4573384"	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/10/08 13:43
2	101	"4522510"	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/10/08 13:43
3	7	"4573384"	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/10/08 13:47
4	101	"4522510"	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/10/08 13:44
-	7	("4634290" "4636088" "4854710" "5003178" "5074669" "6407857" "6583872")	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/10/08 11:48
-	574	electron adj beam adj treatment	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/10/08 11:48
-	326	(electron adj beam adj treatment) and (substrate or wafer)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/10/08 11:59
-	147	((electron adj beam adj treatment) and (substrate or wafer)) and semiconductor	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/10/08 11:49
-	0	((electron adj beam adj treatment) and (substrate or wafer)) and semiconductor) and ((thermal or plasma) adj wave)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/10/08 11:50
-	0	(electron adj beam adj treatment) and ((thermal or plasma) adj wave)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/10/08 11:50
-	5	((("4634290" "4636088" "4854710" "5003178" "5074669" "6407857" "6583872") and ((thermal or plasma) adj wave)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/10/08 13:40
-	326	(electron adj beam adj treatment) and (substrate or wafer)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/10/08 12:00

L Number	Hits	Search Text	DB	Time stamp
1	7	("4634290" "4636088" "4854710" "5003178" "5074669" "6407897" "65838780")	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/10/08 11:48
2	574	electron adj beam adj treatment	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/10/08 11:48
3	326	(electron adj beam adj treatment) and (substrate or wafer)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/10/08 11:59
4	147	((electron adj beam adj treatment) and (substrate or wafer)) and semiconductor	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/10/08 11:49
5	0	((((electron adj beam adj treatment) and (substrate or wafer)) and semiconductor) and ((thermal or plasma) adj wave)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/10/08 11:50
6	0	(electron adj beam adj treatment) and ((thermal or plasma) adj wave)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/10/08 11:50
7	5	((("4634290" "4636088" "4854710" "5003178" "5074669" "6407897" "65838780") and ((thermal or plasma) adj wave)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/10/08 11:55
8	326	(electron adj beam adj treatment) and (substrate or wafer)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/10/08 12:00